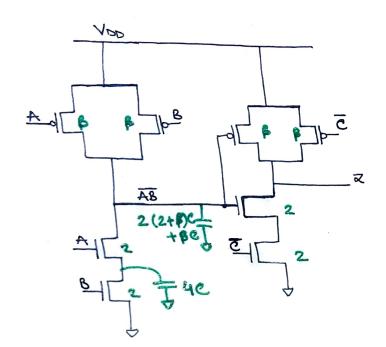
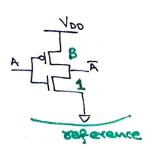
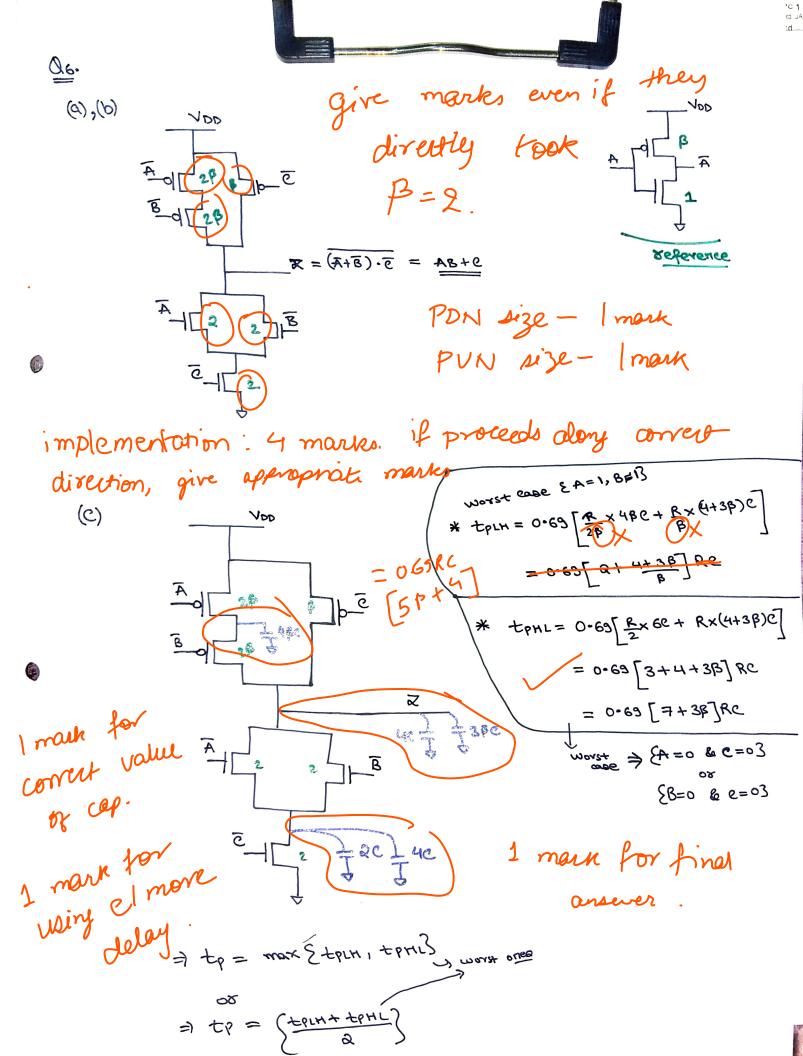
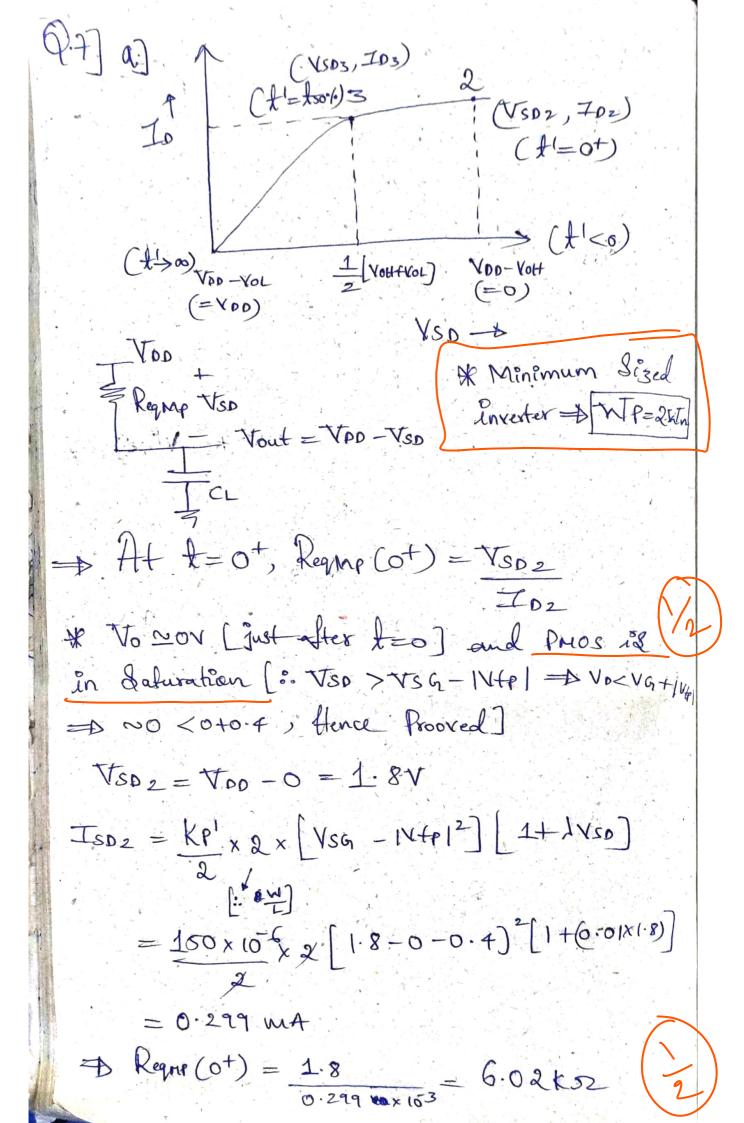
(a), (b), (c)







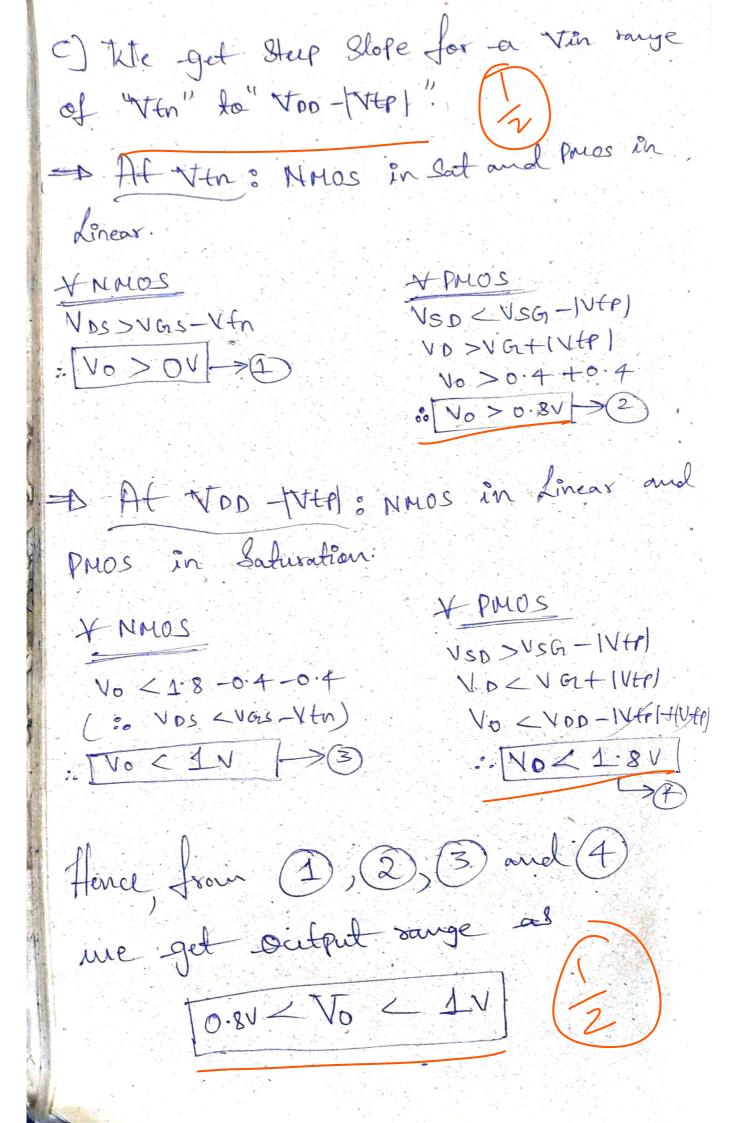


= \$ t= \$0%, Regrap(tso/) = VSO3/ ID3 and il in Linear region (/2 VSD3 = 1 [VOH+ VOL] = = [1.8] = 0.9 V ID3 = Kp. W: [(Vsg-|V+p]) Vso - Vso2]x f 1+ 1 YSD] = $150 \times 10^{6} \times 2 \times \left[(1.8 - 0 - 0.4) 0.9 - \frac{0.9^{2}}{2} \right] \times$ 1+(0.01×0.9) = 258.8085 MA : Reg [\$501.) = 0.9x10 K 52 = 3.477 Ks2 258.8085 => Jotal Reg MP = 1 6.02K+3.477K] = 4.7485KJZ => IPLH = 0.69 CL RegMP =0.69 × 100 × 10 15 × 4.7485 × 103 $= 0.69 \times 4.7485 \times 10^{-10}$ = 3.276465 x 10 10 Seconds

b) Iscmax occurs unless $V_{in} = V_{in}$ The Volume $V_{in} = V$

b) [OR] We get (Isc) wax when both the Txs are in Saturation. from (I) and (2)

The The The state of the s => Vm (1+x) = Vtn + 8[Voo+Vtp] : Vm = Vtn + XLV op + VtP] :X= [+Kplive] Vm=10.4 + [1.8-0.4] 1+(1) Vm = 0.9 V # (Asc) max 70.028 max 60 (Ischus = 0.037 mA

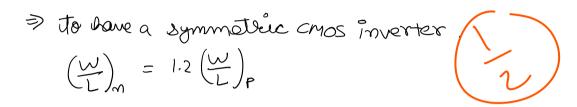


$$(MP)_{SiGe} = 2.4(NP)_{Si}$$

$$= 2.4(NP)_{Si}$$

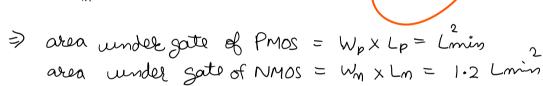
$$= 2.4(NP)_{Si}$$

$$= 1.2 \text{ Mn Si}$$

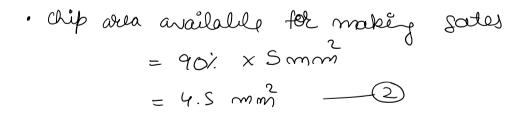


one approach would be to whoose

- · Lm = Lp = Lmin
- · $W_p = W_{min} = L_{min}$ · $W_m = 1.2 W_{min} = 1.2 L_{min}$



=> total area under gates for \ MOSFET = 2.2 Lining __________ = 220 Lmin



equating 1 and 2,

220 Lmin = 4.5 mm

$$\Rightarrow Lmin = \sqrt{\frac{4.5}{220}} \quad mm$$
= 143 μ m

